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DATE MAILED: 10/06/2005

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/812,416	03/30/2004	Tetsuzo Ueda	43890-673	1264
7590 10/06/2005 MCDERMOTT, WILL & EMERY 600 13th Street, N.W.			EXAMINER	
			CRANE, SARA W	
Washington, DC 20005-3096			ART UNIT	PAPER NUMBER
			2811	-

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)				
Office Action Summan	10/812,416	UEDA ET AL.				
Office Action Summary	Examiner	Art Unit				
	Sara W. Crane	2811				
The MAILING DATE of this communication a Period for Reply	appears on the cover sheet with the o	correspondence address				
A SHORTENED STATUTORY PERIOD FOR REF WHICHEVER IS LONGER, FROM THE MAILING  - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory perions are period for reply within the set or extended period for reply will, by stated and the period for reply will, by stated and the period for reply will, by stated and the period for reply will, by stated and patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICATION 1:136(a). In no event, however, may a reply be tire od will apply and will expire SIX (6) MONTHS from tute, cause the application to become ABANDONE	N. mely filed the mailing date of this communication. ED (35 U.S.C. § 133).				
Status						
1)⊠ Responsive to communication(s) filed on 25	S August 2005.					
2a) This action is FINAL. 2b) ⊠ TI						
•	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims	•					
4) ⊠ Claim(s) 1-49 is/are pending in the application 4a) Of the above claim(s) 40-49 is/are withdrest is/are allowed.  5) □ Claim(s) is/are allowed.  6) ⊠ Claim(s) 1-39 is/are rejected.  7) □ Claim(s) is/are objected to.  8) □ Claim(s) are subject to restriction and	rawn from consideration.					
Application Papers						
9) The specification is objected to by the Exami 10) The drawing(s) filed on is/are: a) a Applicant may not request that any objection to the Replacement drawing sheet(s) including the correction.  11) The oath or declaration is objected to by the	ccepted or b) objected to by the he drawing(s) be held in abeyance. Se ection is required if the drawing(s) is ob	ee 37 CFR 1.85(a). ojected to. See 37 CFR 1.121(d).				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for forei a) All b) Some * c) None of:  1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the priority docume application from the International Bure * See the attached detailed Office action for a li	ents have been received. ents have been received in Applicat riority documents have been receiv eau (PCT Rule 17.2(a)).	tion No red in this National Stage				
Attachment(s)  1) Notice of References Cited (PTO-892)	4) ☐ Interview Summan	v (PTO-413)				
2) Notice of References Cited (PTO-892)  2) Notice of Draftsperson's Patent Drawing Review (PTO-948)  3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/(Paper No(s)/Mail Date 2) 13 10 4	Paper No(s)/Mail D					

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## **DETAILED ACTION**

## Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claims 1-39 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

In claims 6, 21, and 30, what is meant by GaN-based epitaxial layers? Is there a base layer of GaN? Or does "based" mean an alloy "based" on GaN? Would such an alloy have to include Ga? (Is AIN "based" on GaN?)

In claim 1, does the film "formed on a substrate" mean the film is in contact with the substrate? Or is the claim using the term "formed on" to mean "formed above"? (As in for example claim 6)

Also, in claim 6, line 2, "layers" is plural but "a" implies the singular.

The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

Claims 6-39 are rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the enablement requirement. The claim(s) contains subject matter which was not described in the specification in such a way as to enable one skilled in the art to

which it pertains, or with which it is most nearly connected, to make and/or use the invention.

The specification does not seem to teach how to form a "GaN-based epitaxial layers having a 4H-polytype structure" as recited. Page 11, lines 17-21, teaches growth parameters for the AlN buffer layer, but lines 22-23 say only that the 4H-GaN layer is grown by MOCVD. Wouldn't one of ordinary skill need to know all of the growth parameters such as those given for the AlN layer, in order to grow the GaN layer without undue experimentation? Examiner's understanding is that careful optimization is needed in order to end up with the desired 4H structure (?) Or would any MOCVD growth process whatever give the 4H result? It seems that the most important part of the teaching was simply left out of the specification.

Claims 1-5 are rejected under 35 U.S.C. 112, first paragraph, because the specification, while being enabling for an AIN film having 4H-polytype, does not reasonably provide enablement for BInAlGaN having 4H-polytype. The specification does not enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to practice the invention commensurate in scope with these claims.

The single embodiment of AIN does not provide enablement for all of the compositions included in the scope of claim 1. Each different material would require its own set of growth conditions, and undue experimentation would be required for any alloy other than the AIN as taught in the specification.

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to S. Crane, whose telephone number is (571) 272-1652.

The supervisor for Art Unit 2811, Eddie Lee can be reached on (571) 272-1732. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Sara W. Crane Primary Examiner

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